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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Ibrahim Abdulhalim, et al.
Title: Periodic Patterns And Technique To Control Misalignment Between Two Layers
Application No.: 09/833,084 Filing Date: April 10, 2001
Examiner: Zandra V. Smith Group Art Unit: 1775
Docket No.: TNCR.196US0 Conf. No.: 8866

Certificate of Mailing Under 37 CFR 1.8

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Signature

Tracy M. Smith

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 to the Examiner's attention in this patent application.

Copies of the documents listed on the accompanying Form PTO-1449 are enclosed.


Citation of these documents shall not be construed as (1) an admission that the documents are prior art with respect to the invention or inventions claimed in this application, (2) a representation that a search has been made (other than as indicated by any cited document), or (3) an admission that the cited information is, or is considered to be, material to patentability as defined in § 1.56(b).

Attorney Docket No.:
TNCR.196US0

Application No.:
09/833,084

This information disclosure statement is submitted under 37 C.F.R. § 1.97(b) and consequently no fee should be required. The Commissioner is authorized, however, to charge any fee that may be required, or to credit any overpayment, against Deposit Account No. 502664. This form is being submitted in duplicate.

Respectfully submitted,


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U.S. Department of Commerce, Patent and Trademark		Atty. Docket No.	Application No.
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(Use several sheets if necessary)		Applicant(s)	Conf. No.
		Ibrahim Abdulhalim, et al.	8866
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							Translation	
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Examiner		Date Considered	
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>			